



ARES NO_x Sensor Development

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Project Description, Goals, and Objectives

- Develop new, low cost, solid-state sensors to detect NO_x in the exhaust gas stream of a reciprocating engine.
 - Ceramic sensors that operate on electrochemical principles
- Sensors to control regenerative NO_x catalyst systems.
- Sensors must be inexpensive, robust, and be able to detect NO_x in regimes of PO₂, T, [NO_x] characteristic of current engine technology
- Lifetime, stability, sensitivity, response time, sulfur tolerance, device reproducibility, cost, etc.



Project Team - LANL

- LANL team has 10 years of experience in the development of gas sensor technology
 - Oxygen
 - Sulfur dioxide
 - Hydrocarbons
 - Carbon monoxide
 - Nitric oxides
- LANL CRADA with USCAR to develop high temperature electrochemical sensors for OBD-II applications.
- FY 1997 - 2001
 - Sensors required to measure real-time NMHC concentration
 - Partners: Ford, GM, and Chrysler
- 4 Patents issued in sensor technology



Project Team

■ Previous LANL sensor work examples:

- LDRD sensor development work
 - ★ “Controlled Interface Gas Sensors”, U.S. Patent applied for 2002.
- Sulfur resistant O₂ combustion control sensors
 - ★ Winner 1999 R&D 100 award in collaboration with Rosemount Analytical Co.
 - ★ U.S. Patent no. 6,277,256
- Amperometric response, lean burn O₂ sensor work in collaboration with Delphi Automotive
 - ★ U.S. Patents 5,695,624 & 5,543,025

- ## ■ University Collaboration : ARES NO_x sensor development work performed in collaboration with Dr. Eric Wachsman and his sensor team at the University of Florida



Impact on Goals of ARES Program

- Advanced reciprocating engines require new sensor technologies to reduce emissions and improve over-all efficiency.
 - NO_x emissions monitoring and control
 - Engine control
 - Control of NO_x regeneration catalysts and systems
- E.g. NO_x emissions cannot exceed 50 - 150 ppm (0.1 g/hp-hr).
- A NO_x sensor is needed to monitor and control emissions systems.
- Currently there is no suitable sensing technology available that is low-cost sulfur tolerant, long-lifetime, etc.



ARES Emissions Information

Event Comment		Lean Limit				Detonation Limit
Engine Speed	rev/min	1499	1499	1500	1500	1500
Air/Fuel Stoich	kg air/kg fuel	16.04	16.04	16.04	16.04	16.05
	kg air/kg fuel	31.65	30.09	29.35	28.88	28.17
Air/Fuel Ratio	none	0.51	0.53	0.55	0.56	0.57
Equivalence Ratio						
Turbocharger Efficiency	%	64.02	64.30	64.60	64.68	65.01
Oxides of Nitrogen	ppm	35	141	280	445	872
Carbon Monoxide	ppm	441	376	405	432	472
Carbon Dioxide	%	5.99	6.45	6.59	6.75	6.95
Unburned Hydrocarbons	ppm	2413	1758	1636	1565	1457
Exhaust Oxygen Content	%	10.86	10.09	9.83	9.55	9.19

Table 1. Exhaust gas data for advanced reciprocating engines operating under differing conditions.

- NO_x sensors need to operate in an environment with oxygen, HC's (CH₄), carbon dioxide, and carbon monoxide

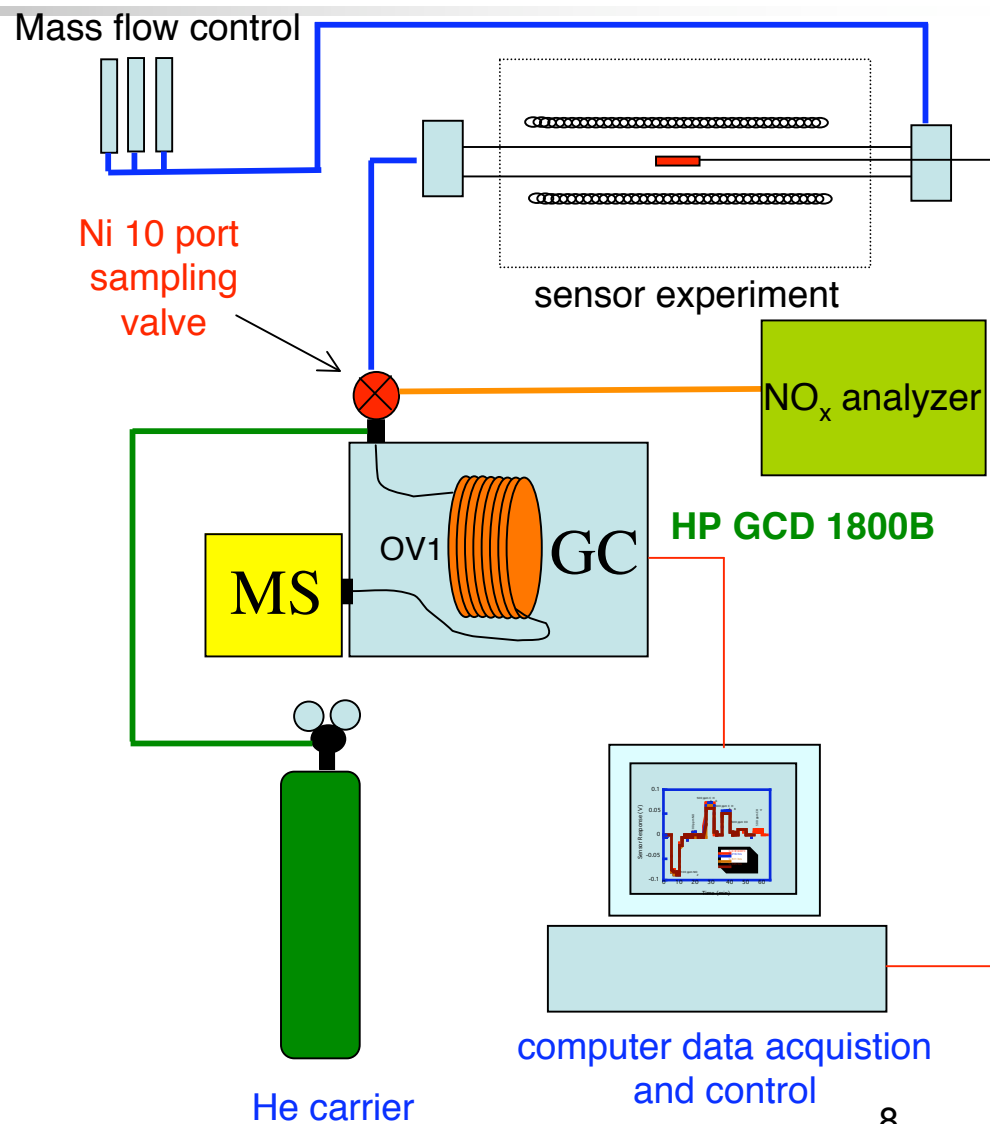


Milestones completed and planned

- Assemble analytical NO_x capability at LANL with resources that are available. **Completed**
- Fabricate devices for initial study to demonstrate proof-of-concept. **Completed**
- Test and calibrate analytical [NO_x] system and build new test stations. **Completed**
- Study factors that affect sensitivity, lifetime, response time. **Work In Progress**
- Study electrode materials - NO_x catalysis and electrocatalysis. **Work In Progress**
- Study electro-catalysis and NO_x mixed potential electrochemistry. **Work In Progress**
- Improve NO_x sensor. **Work In Progress**
- Identify industrial partners for sensor commercialization. **Work In Progress**

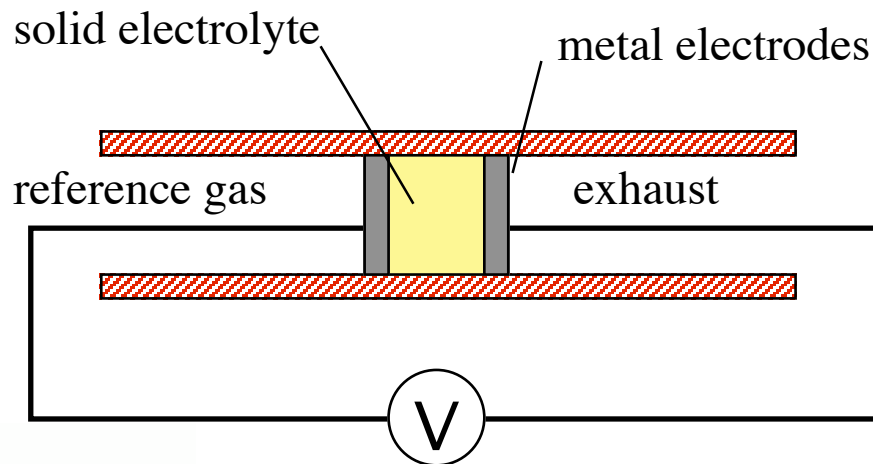
Development of NO_x Analysis Capability

- Develop NO_x and interference gas analysis system
- First task was to build an in-house NO_x measurement capability.
 - [NO_x] changes over time
 - Complex equilibrium in presence of O₂
- Horriba analyzer for NO_x
- GC/MS system used to characterize interference gas concentrations



Nernstian Sensor Response

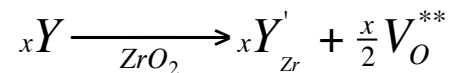
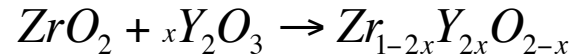
- Oxygen ion electrolyte, Pt electrodes
 - $t_{\text{ion}} \gg t_e$
- Nernst equation obeyed if only oxygen is involved in electrochemical reactions
 - Oxygen- nitrogen mixtures



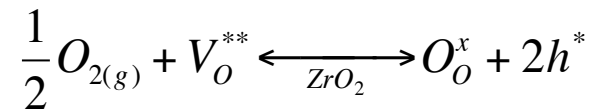
$$E = -\frac{RT}{4F} \ln \left(\frac{P_{\text{O}_2}'}{P_{\text{O}_2}''} \right)$$

Sensor Theory (Interfaces)

- Zirconium oxide is doped with yttrium oxide to produce lattice vacancies:



- defects in zirconia electrolytes are charged:



- Surface concentration of vacancies are much lower than bulk in air
 - Minority electronic carriers present at surface can diffuse across solid electrolyte/electrode interface

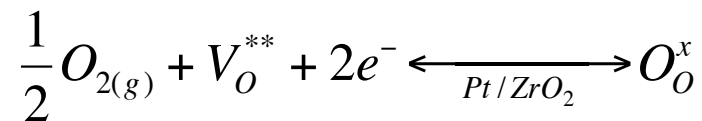
$$E_{F(elect)} = \mu_e + zq\phi$$

$$j_D + j_\phi = 0$$

$$0 = c \frac{D}{kT} \frac{d\mu}{dx} + \frac{zqD}{kT} c \frac{d\phi}{dx}$$

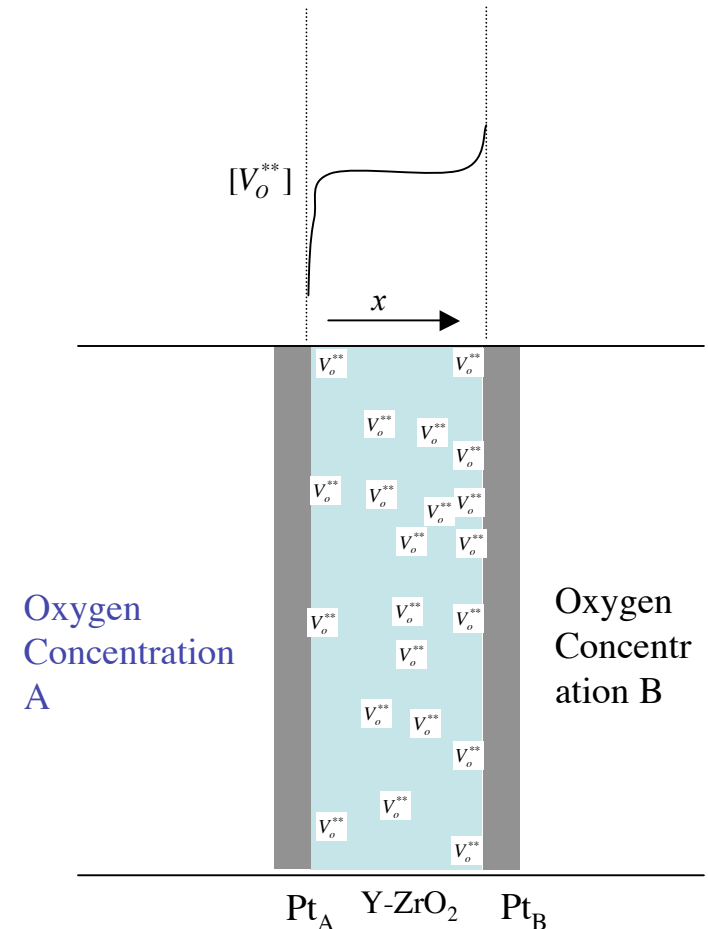
Sensor Theory

- Charged defect activity and concentration at surfaces controlled by chemical eq.



$$\Delta\phi_{Pt,AB} = \frac{RT}{nF} \ln \frac{(a_{O_2, PtB})}{(a_{O_2, PtA})} = \frac{RT}{nF} \ln \frac{(a_{V_O^{**}}(ZrO_2, B))}{(a_{V_O^{**}}(ZrO_2, A))}$$

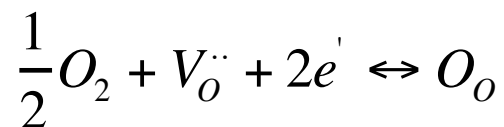
$$a_{V_O^{**}}(ZrO_2) = \gamma[V_O^{**}]$$





Multiple Redox Gases

- More than one reaction can control charged species activities at sensor interfaces:



- Reactions need to be divided into elementary steps with kinetic rate constants k_i
- Extremely complex due large number of elementary reaction steps

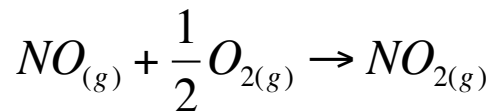
Reactions Before Triple Phase Boundary

- As the gases diffuse to triple phase boundaries chemical reactions change gas concentrations

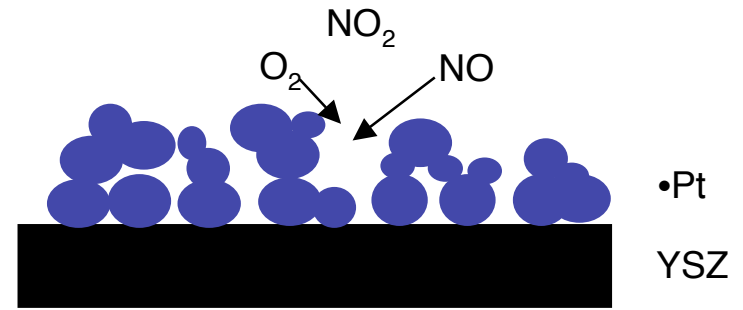
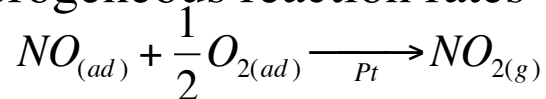
- gas diffusion rates and mechanisms

$$D \propto \sqrt{m_g / kT}$$

- homogeneous reaction rates



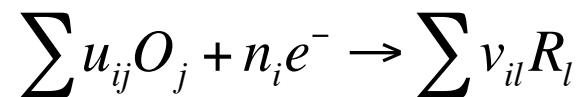
- heterogeneous reaction rates





Mixed Potential Representation Of Reaction Rates Near TPB

- For multiple parallel redox processes the potential of the electrode is determined by kinetic reaction rate constants (k) and activities (a) of the individual species:

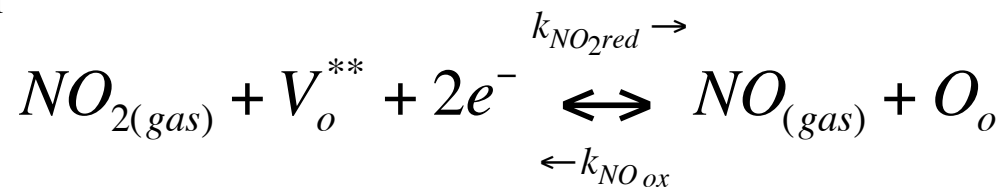
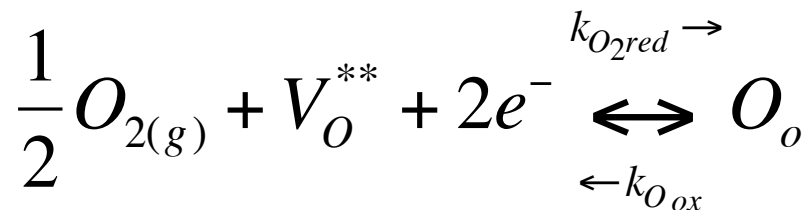


$$\Delta\phi_{electrode} = \left[\frac{RT}{nF} \ln \frac{\sum k_{ri} \prod a_{O_j}^{u_{ij}}}{\sum k_{oi} \prod a_{R_l}^{v_{il}}} \right]$$

- Many of the elementary rate constants are included in the redox reaction rate constants
- For a zirconia sensor the interfacial concentration of charged species is controlled by the triple phase boundary reaction rate kinetics

Kinetic Devices

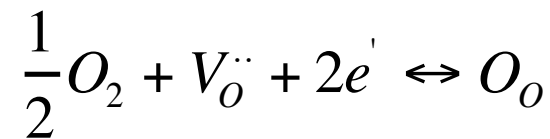
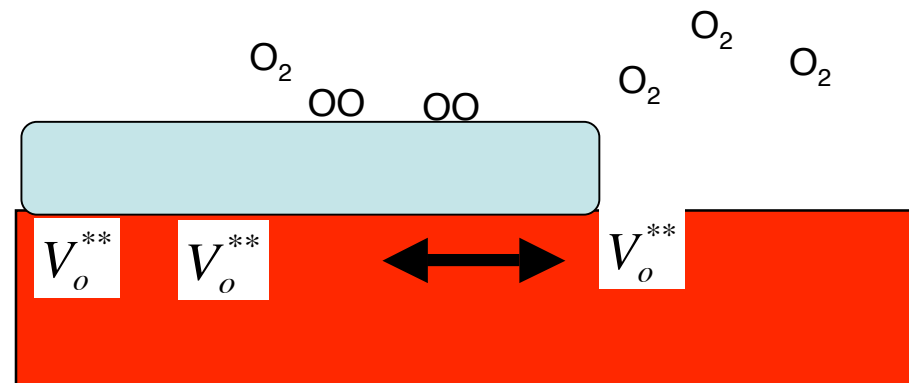
- Exploit the differences in electrode reaction rate kinetics with electrolyte ion to increase sensitivity to target gas
- Knowledge of electrode catalysis reactions needed
- Need electrode materials with high rate constants k for nitric oxide reactions for sensing electrode
 - Perovskite oxides: ABO_3
 - Spinel oxides: AB_2O_4
- Lanthanum chromium oxide perovskites LaMCrO_3 compounds
 - $\text{M}=\text{Mg, Ca, or Sr}$
- Spinel: ZnFe_2O_4 , NiCr_2O_4



Sensor Response Kinetics

- Rate determining steps:
 - Adsorption of Oxygen
 - Diffusion to TPB
 - Charge transfer
 - Diffusion of oxide ions, holes along Pt electrode/electrolyte interface to equilibrate potential

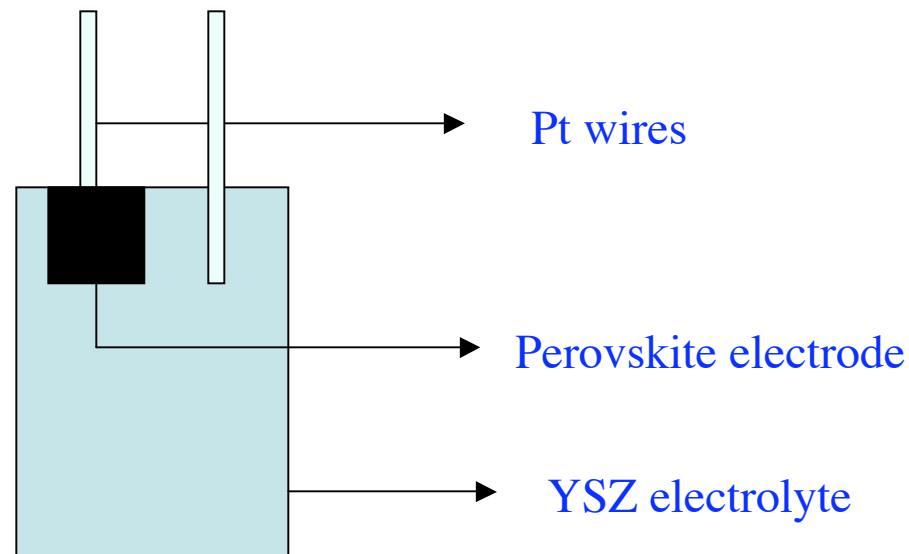
- Diffusion of oxide ions via a vacancy mechanism to/from triple phase interface rate limiting in most cases
 - Fine grain size porous electrodes respond fastest



$$\tau_{sensor} \propto \frac{x^2}{D}$$

Sensor Design

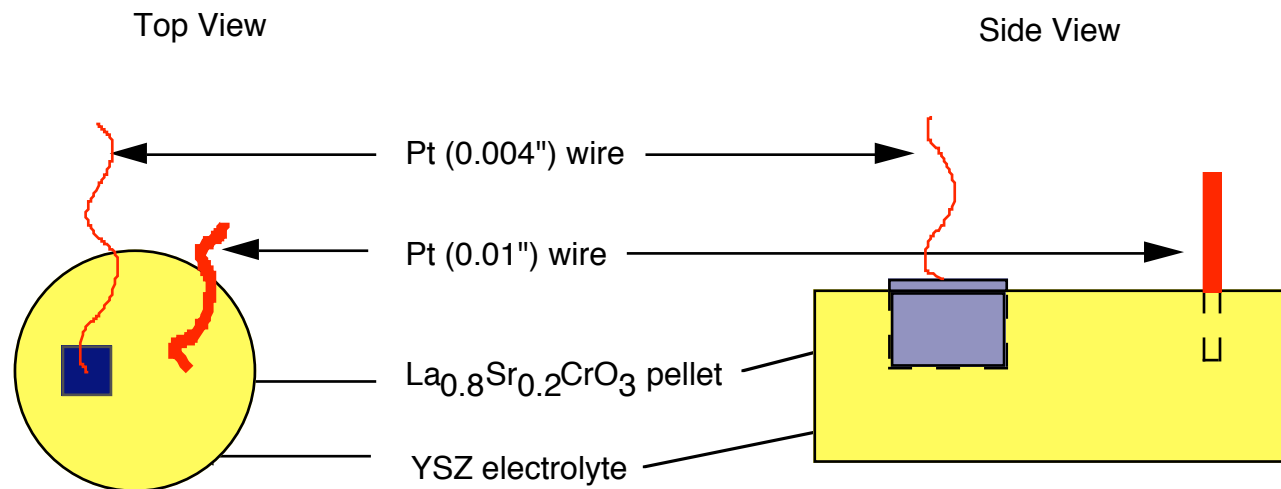
■ Controlled Interface



- Wire and pellet electrodes in an electrolyte pellet
 - Stable, defined 3 phase interface

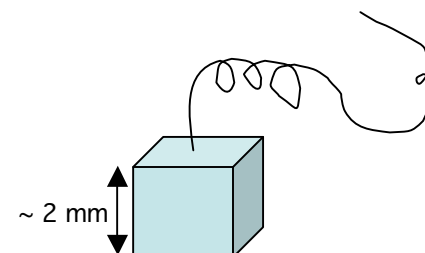
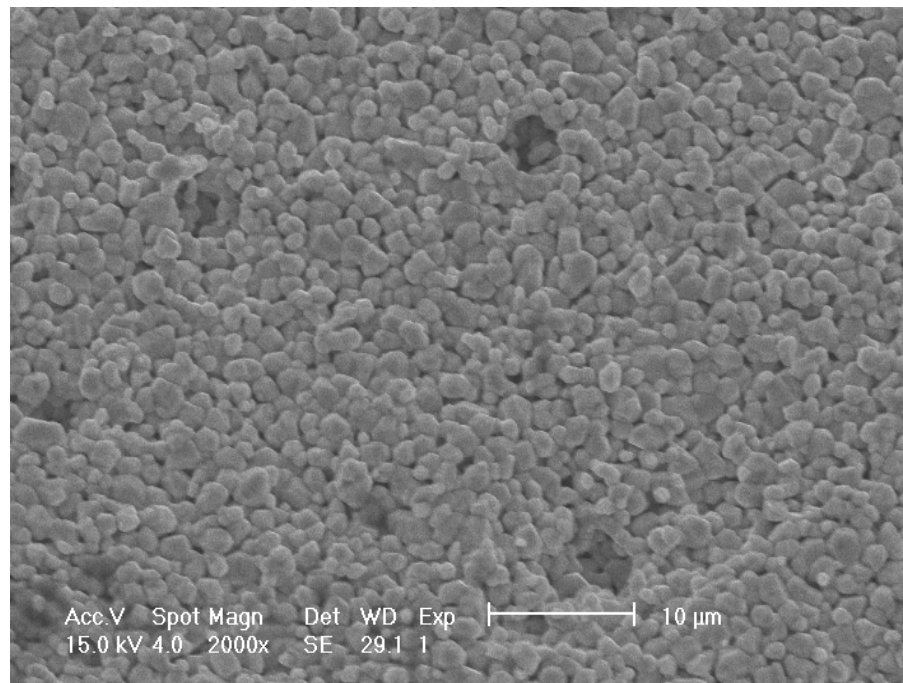
Sensor Design

- Control the three-phase interface and surface area by pressing a dense pellet of $\text{La}_{0.8}\text{Sr}_{0.2}\text{CrO}_3$ and a Pt-wire into YSZ and co-sintering

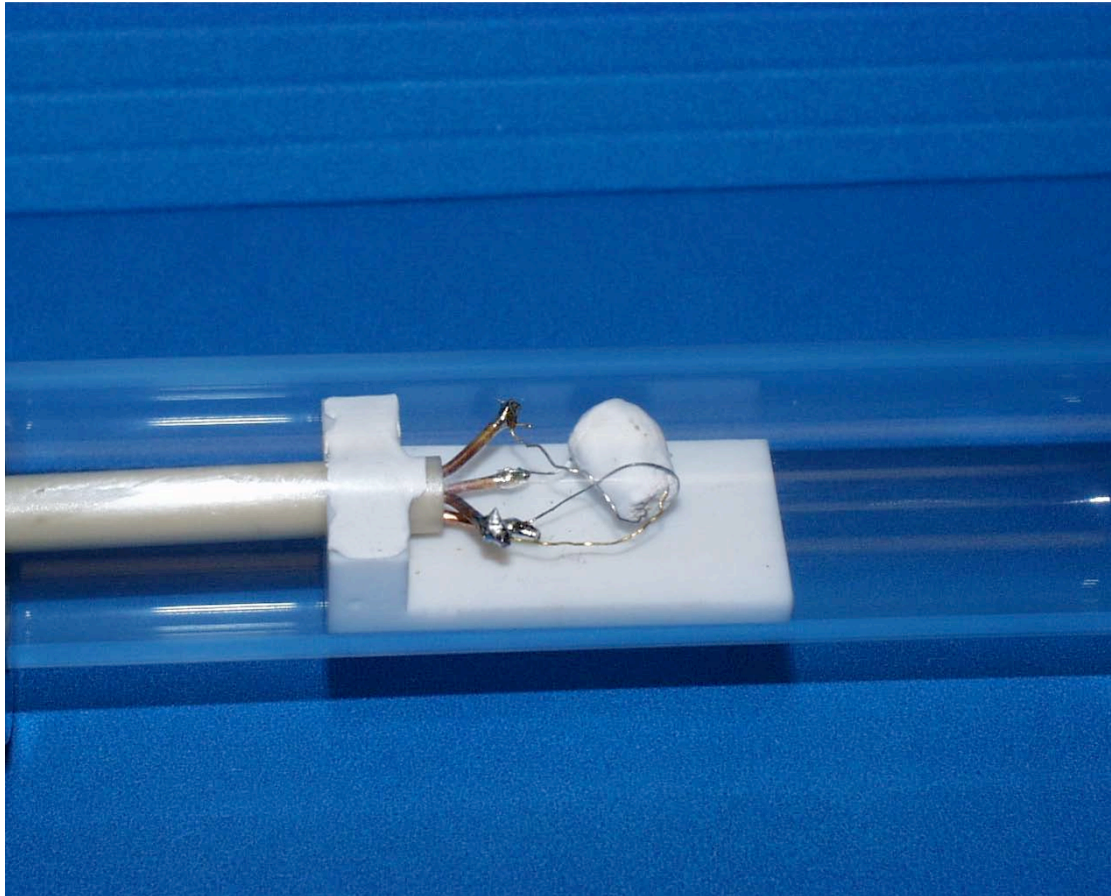


Bulk Preparation of LaMCrO_3 Electrode for Mixed Potential Sensors

- Commercial powder purchased from Praxair Corp.
- Lanthanum chromites made from spray pyrolysis process
- Electrode formed by isostatic pressing powder and sintering at 1650°C for 10 hours in air.
- Cube shape cut using a diamond saw.
- Pt wire embedded during sintering to make electrode for “bulk” type, mixed potential sensor.



Ceramic Sensor With Heater





Thin Film Sensor Development

- Thin film devices are more desirable than bulk ceramic devices
 - Low cost lithographic manufacturing techniques
 - Smaller sized
- Experimental
 - RF magnetron sputtering via oxide target
 - RF magnetron sputtering via fluoride target / precursor film
 - Electron beam and thermal evaporation
 - Pulsed laser deposition using fluoride and oxide composite targets
- Film Characterization
 - XRD, SEM, XRF characterization

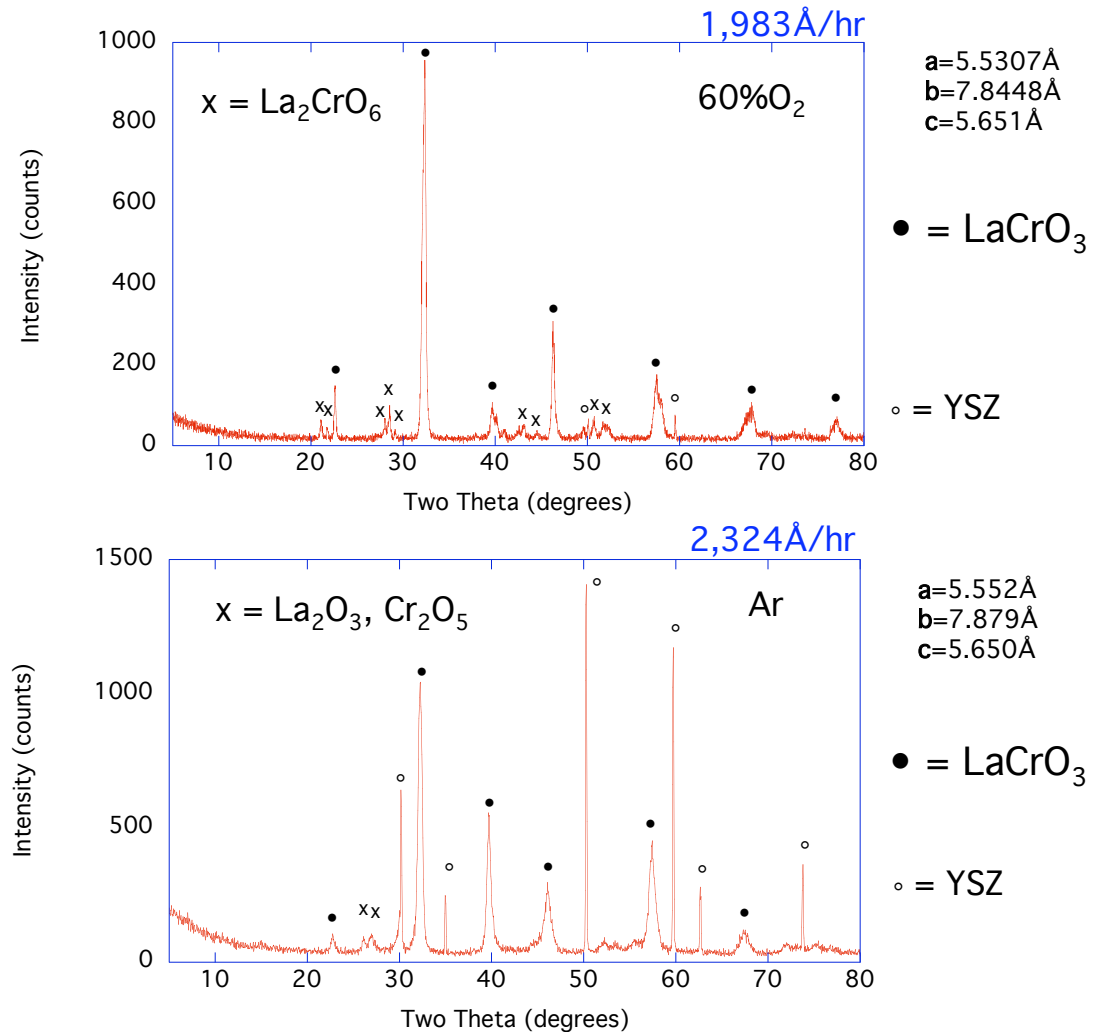
RF Sputtering Using Fluoride Targets

- Target fabricated using mixture of LaF_3 , SrF_2 , and Cr metal
- Ball-milled 6 hrs using alcohol and zirconia grinding media
- Powder was pressed into 2" diameter die and pressed at 400 lbs
- Target heated at $2^\circ\text{C}/\text{min}$ in dry Ar to 1100°C and held for 500 min to sinter
- Sintered target was mounted to a 2" dia Cu sputter cup using Ag epoxy
- Poly-crystalline Al_2O_3 , sapphire, or CeraFlex™ brand YSZ wafers were used as substrates
- Typical sputter conditions: 40 mTorr, UHP Ar 90° off axis, 125W RF
- Substrate temperature either left to float at ambient or 400°C



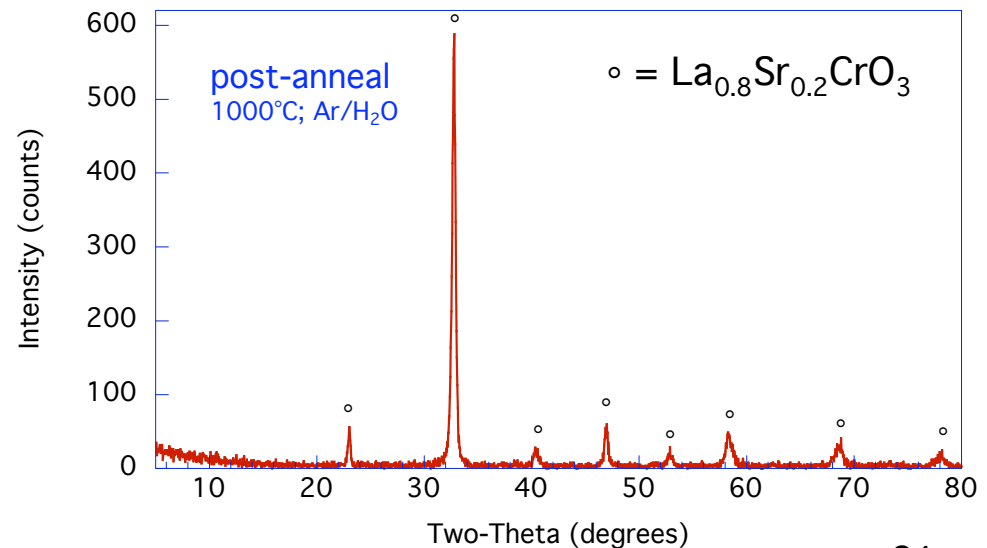
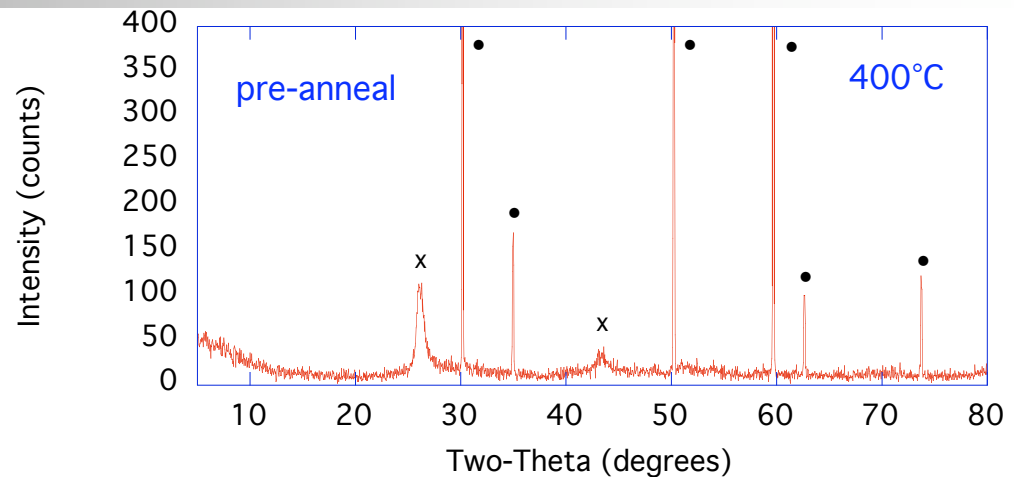
RF Magnetron Sputtering - Oxide Target Deposition

- CeraFlex™ brand YSZ wafers or polycrystalline Al_2O_3 and sapphire used as substrates.
- Commercial $\text{La}_{0.8}\text{Sr}_{0.2}\text{CrO}_3$ sputter target purchased from Praxair.
- Sputter conditions:
 - 40 mTorr sputter pressure
 - 60% O_2/Ar or UHP Ar
 - on-axis orientation to maximize deposition rate
 - 125W of RF power
 - $T = 650^\circ\text{C}$

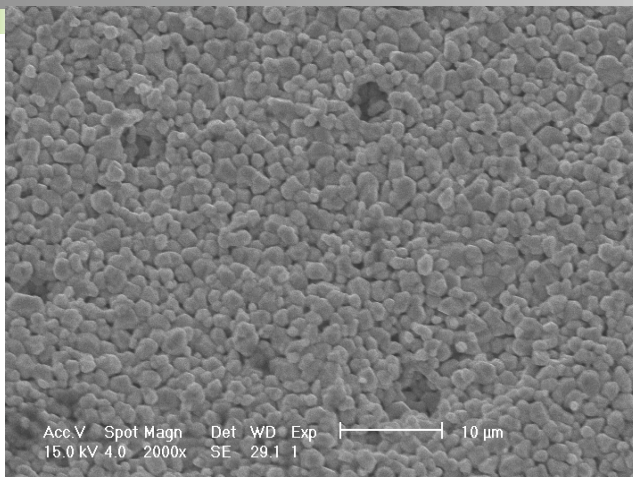


RF Magnetron Sputtering - Fluoride Process

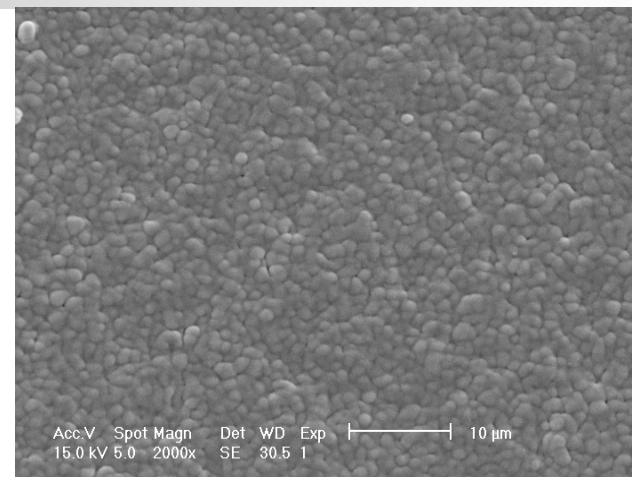
- Off-axis orientation required.
- Composite films deposited at 400°C exhibited good adhesion $T_{\text{sub}} = 400^\circ\text{C}$
- Ar atmosphere, 40 mTorr
- 1.2 μm (oxide thickness), 8 hrs deposition time
 - 1500 Å/hr
- $a=5.4523\text{Å}$, $b=5.4523\text{Å}$
 $c=13.443\text{Å}$ agrees well with literature data



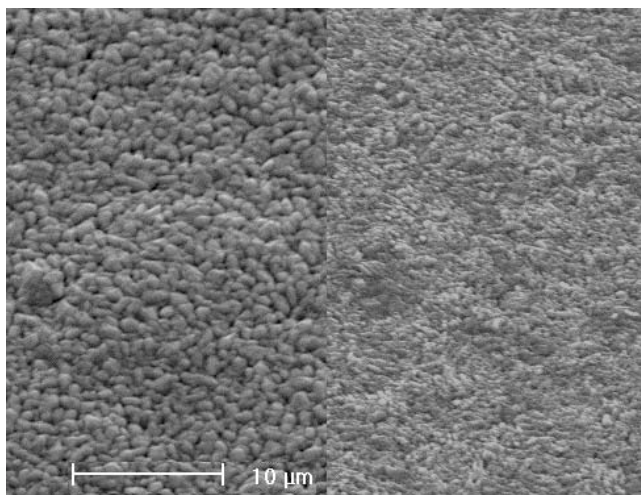
Thin Film SEM Analysis



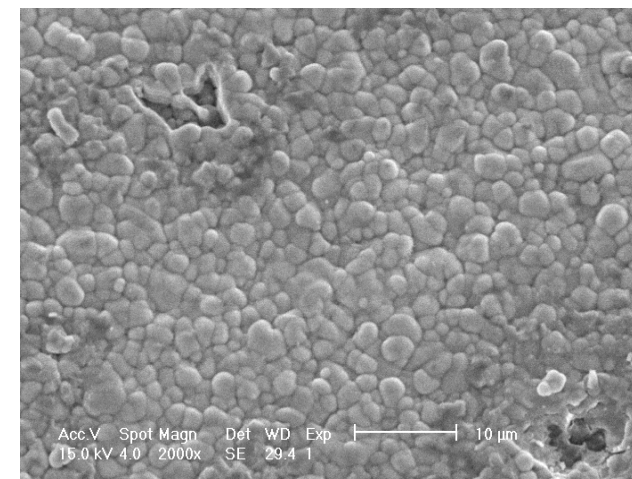
Bulk sintered material: 1650°C, 10hrs



RF magnetron sputtering / fluoride
400°C dep / 1000°C post anneal



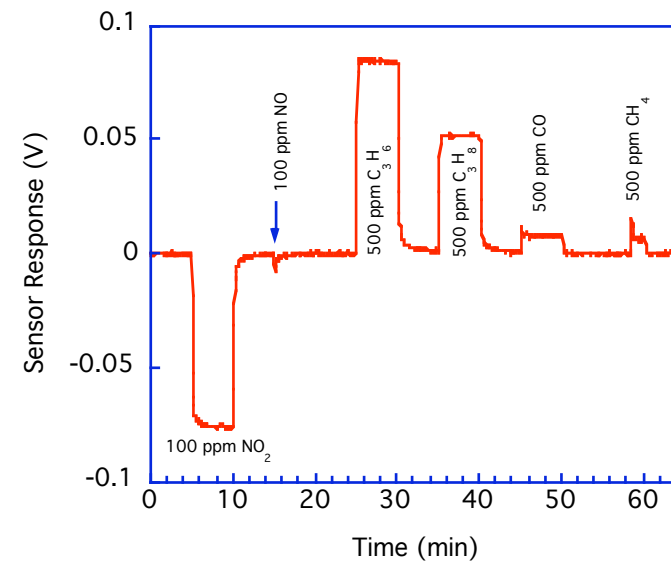
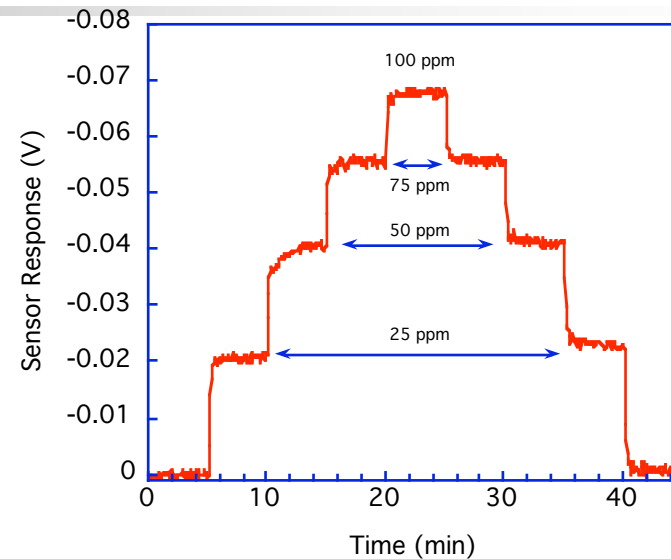
RF magnetron sputtering / oxide
650°C deposition T / Ar



Electron beam/thermal evap. / fluoride
400°C dep / 1000°C post anneal

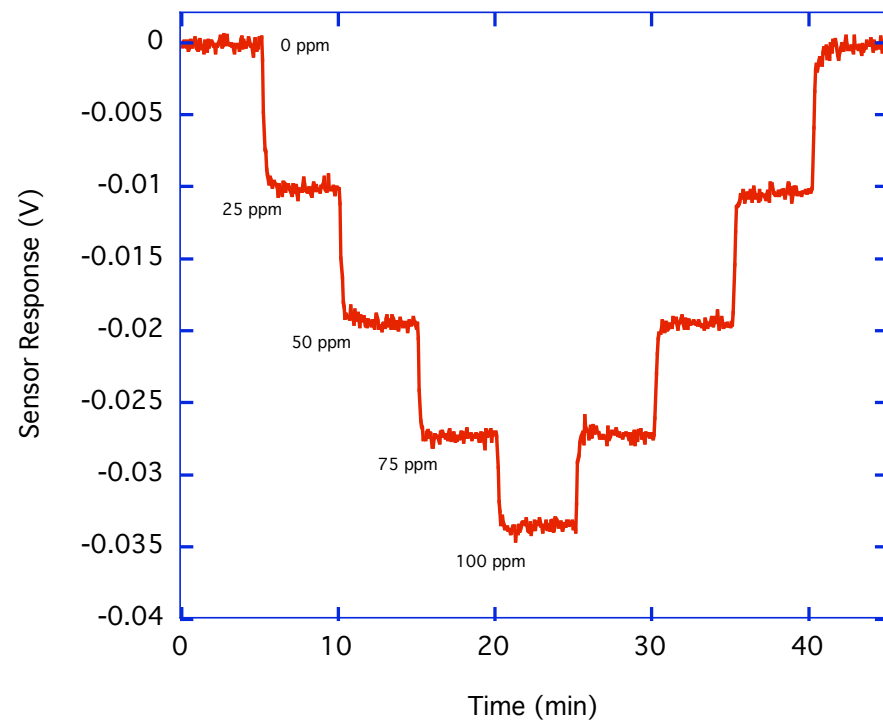
Thin Film Sensor Results

- Different metal oxide electrode selected based on observations of higher NO_x catalysis.
 - $\text{LaCr}_{0.8}\text{Mg}_{0.2}\text{O}_3/\text{YSZ}/\text{Pt}$
- Initial testing performed hot - 650°C and in $1\%\text{O}_2$
- Mixed potential response to NO_2 with no sensitivity to NO .
- Interference to CO and HC 's
 - almost 5:1 sensitivity to NO_2



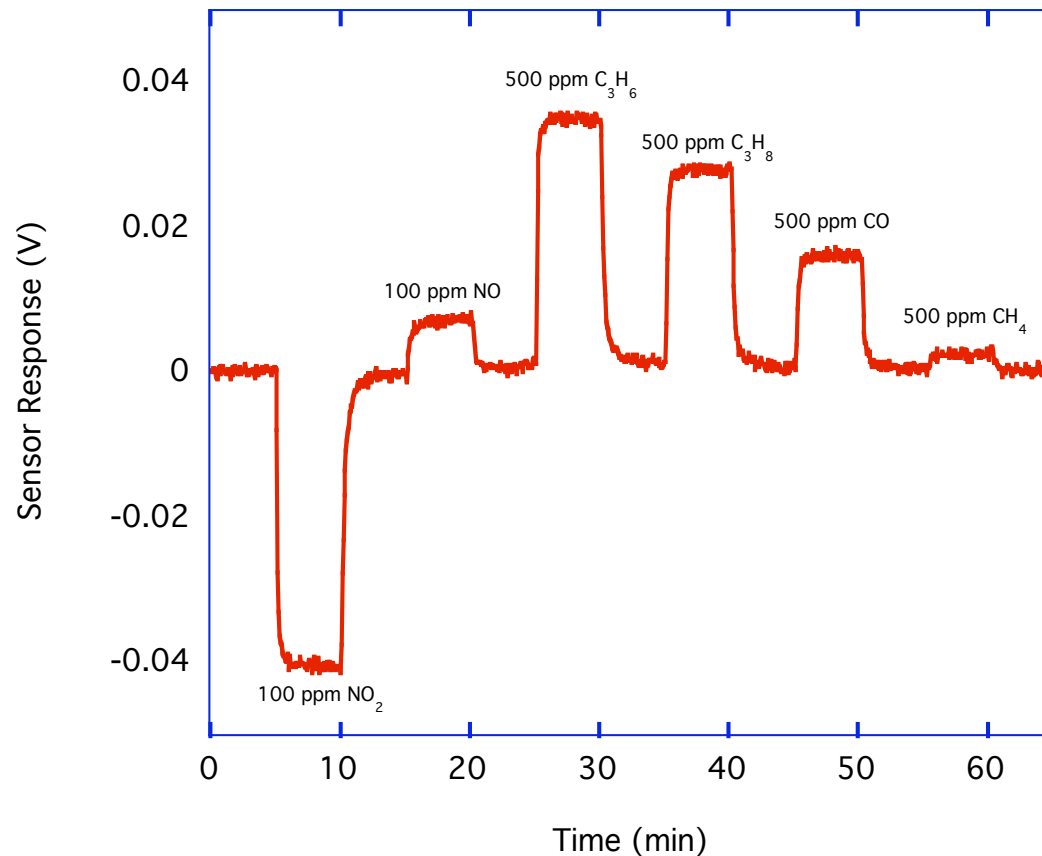
Response To Varying Levels of NO₂

- NO₂ response at 650°C, 10.4 % O₂/N₂ balance flowing at a base flow rate of 500 SCCM
- Reproducible response as gas concentration is stepped both up and down



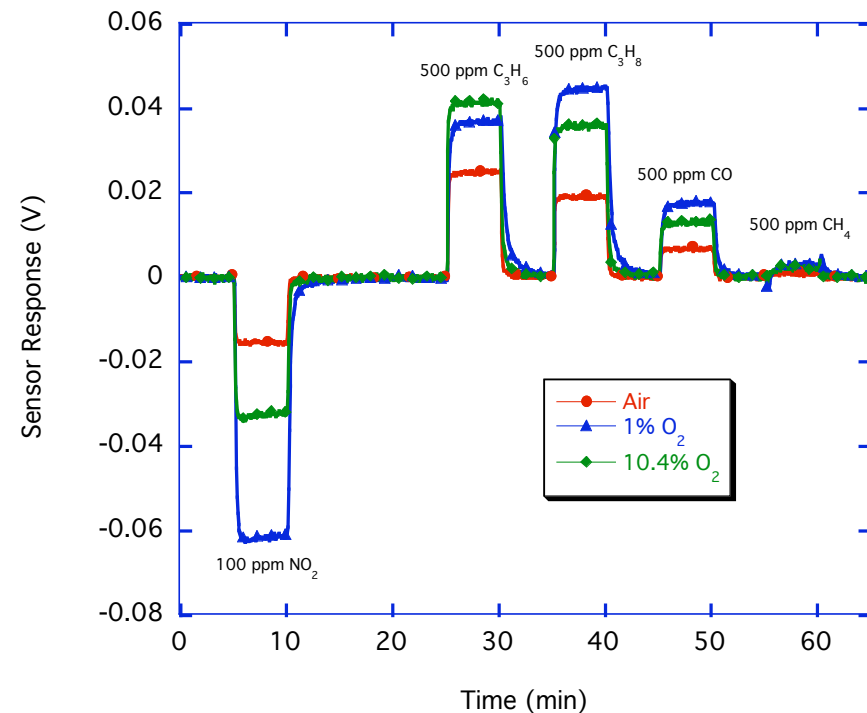
Thin Film Device Response 2000 hrs

- Thin film sensor
 $\text{LaCr}_{0.8}\text{Mg}_{0.2}\text{O}_3/\text{YSZ}/\text{Pt}$
- Sensor response to NO_2 , NO , and selected HC's and CO versus time at 600°C after device testing at 650°C . Base gas is 10.4% O_2 at a flow rate of 500 SCCM.
- Response after 2000 hrs testing



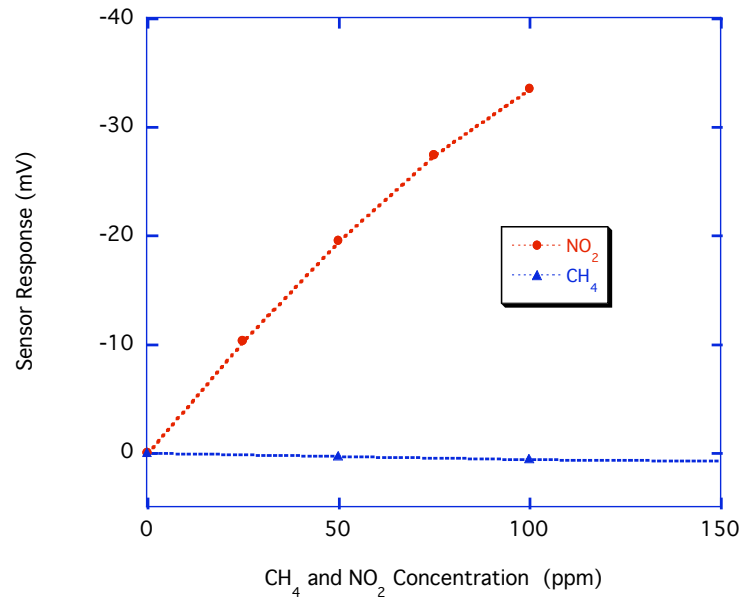
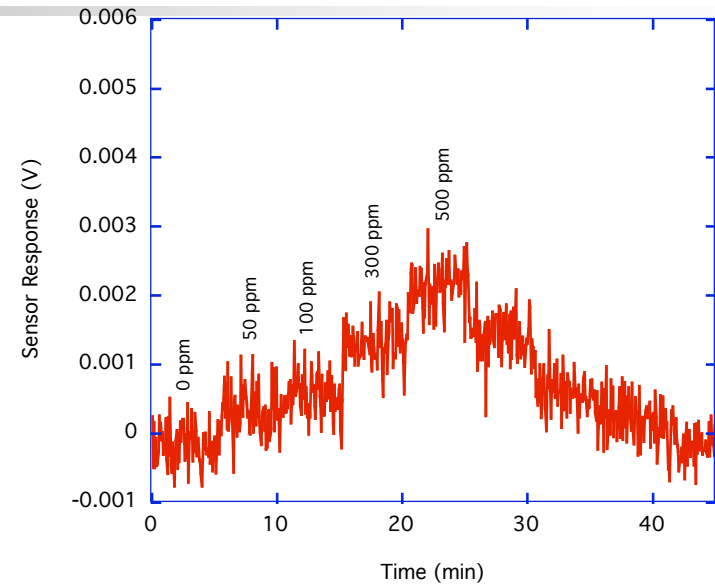
Oxygen Concentration Effects

- Sensor response at 650°C
- Sensor response must be calibrated as a function of oxygen pressure
- Use lambda sensor to provide oxygen concentration



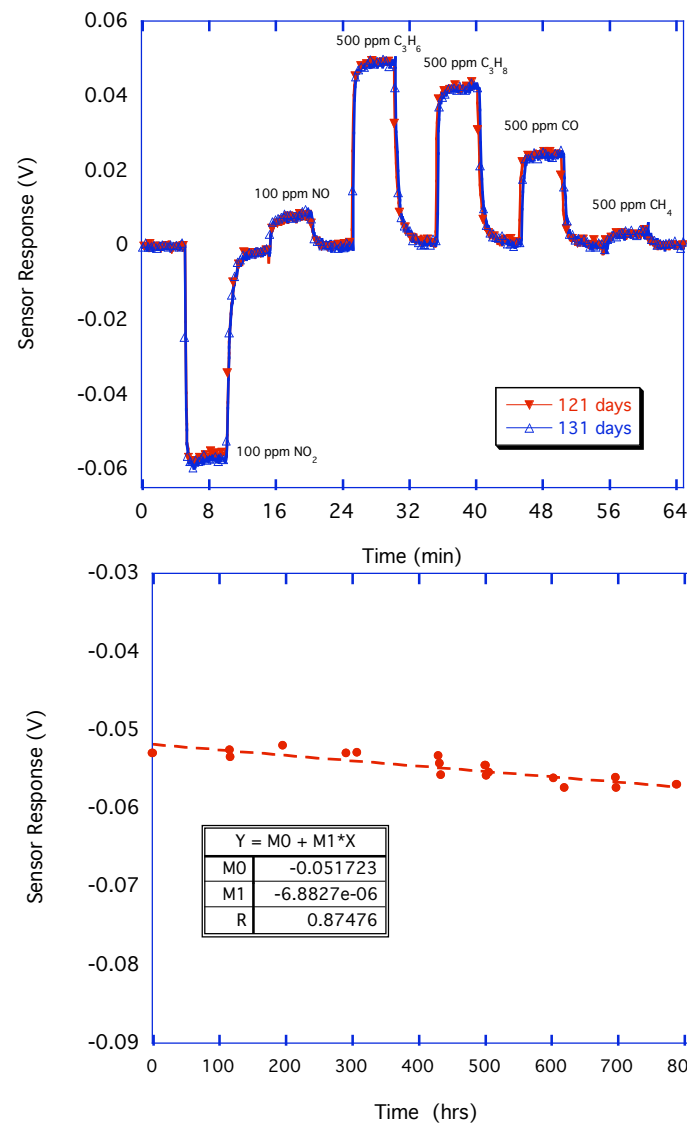
Methane Cross Interference Testing

- CH₄ response at 650°C, 10.4 % O₂/N₂ balance flowing at a base flow rate of 500 SCCM.
- Almost no methane cross interference



Long Term Testing

- Sensor response to NO_2 , NO , and selected HC's and CO versus time at 121 and 131 days of lifetime testing at 600°C . Base gas is 10.4% O_2 at a flow rate of 500 SCCM
- NO_2 response for 800 hours of testing





Key Technical Barriers and Project Risks

- Key technical barriers are:
 - Designing sensors with adequate sensitivity and selectivity
 - Elimination of cross interferences
 - Response stability over sensor lifetime
 - ★ Electrode ageing phenomena
 - Low cost requirements



Summary

- LANL NO_x sensor work commenced in February 2002
- Assembly of gas chromatography/mass spectroscopy system combined with a Horriba NO_x system complete
- Developed fabrication methods for both ceramic and thin film mixed potential based NO_x sensors
- Investigated nitric oxide and cross interference gas responses
 - Good sensitivity to NO₂
 - No CH₄ interference
- Investigation of long-term sensor response stability
 - Over 2000 hrs for some devices
- Preliminary contacts with sensor suppliers
 - Dephi, and Figaro USA
- Continuing sensor optimization work
- Development of theoretical models



Publications and Patents

■ Publications and Presentations

- F. H. Garzon, R. Mukundan and E. L Brosha “Solid State Ionic Devices For Combustion Gas Sensing” submitted to *Solid State Ionics* 2003
- Eric L. Brosha, Rangachary Mukundan, David R. Brown, Q. X. Jia, Roger Lujan, and Fernando H. Garzon, “Techniques for the Thin Film Growth of $\text{La}_{1-x}\text{Sr}_x\text{CrO}_3$ for Solid State Ionic Devices,” submitted to *Solid State Ionics*, July 2003.
- Eric L. Brosha, Rangachary Mukundan, and Fernando H. Garzon, “The Role of Heterogeneous Catalysis in the Gas-Sensing Selectivity of High-Temperature Mixed Potential Sensors,” proceedings of the 202nd meeting of the Electrochemical Society, Salt Lake City, Utah, October 21-25, 2002.
- Fernando H. Garzon, Eric L. Brosha, Rangachary Mukundan, “The Evolution of High Temperature Gas Sensors,” presented at the 201st meeting of the Electrochemical Society, Philadelphia. May 2002.

■ Patents

- S-99,902 - ELECTRODES FOR SOLID STATE GAS SENSOR Patent granted
- S-100,655 - THIN FILM MIXED POTENTIAL SENSORS-Patent disclosure in Process of filing